

Amendment to Specification

On page 38 of the specification, replace paragraph 00115 with the following:

[00115] A sample on substrate 320 passes through the several sections of the process. The substrate 320 enters the first dimension buffer reservoir 306 where the substrate 320 is saturated with first buffer. The substrate 320 is conveyed on a conveyor or substrate support 322 to a first dimension separation region 330. The substrate is then conveyed through the first dimension buffer reservoir 308, followed by an optional first rinse reservoir 340. The substrate is then transferred to a substrate reservoir 350 where the substrate 320 is saturated with second buffer, and then through the second buffer reservoirs 312 containing second dimension electrodes 310 and spanning second dimension separation region 360. The conveyor transports the substrate optionally through a second wash reservoir 370 and/or dye solution reservoir 380 followed by an optional third wash reservoir 390. Lastly, if desired, the substrate may be conveyed through a drying chamber 400. In the 1D variant (not shown), second dimension electrodes 310 and buffer reservoirs 312, second dimension separation region 360, and second wash reservoir 370 are not needed. A housing 410 may be incorporated below the conveyor to catch any leaking liquids.